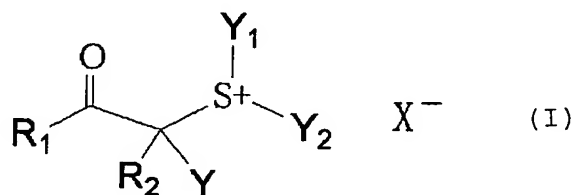


1. A photosensitive composition comprising a compound capable of generating an acid upon irradiation with an actinic ray, the compound being represented by the following general formula (I):



R<sub>2</sub> represents a hydrogen atom, an alkyl group, or an aryl group;

Y<sub>1</sub> and Y<sub>2</sub> may be the same or different and each represents an alkyl group, an aryl group, an aralkyl group, or a heteroatom-containing aromatic group;

R<sub>2</sub> and Y may be bonded to each other to form a ring;

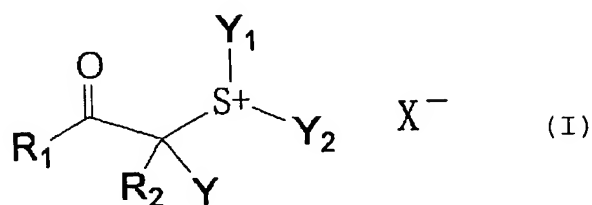
two or more structures of the general formula (I) may be bonded to each other at any position of R<sub>1</sub>, R<sub>2</sub> or Y, or Y<sub>1</sub> or Y<sub>2</sub> via a connecting group; and

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2. A positive photosensitive composition comprising:

(A) a compound capable of generating an acid upon irradiation with an actinic ray, the compound being represented by the following general formula (I); and

(B) a resin that is decomposed by the action of an acid to increase its solubility in an alkaline developer:



wherein  $\text{R}_1$  represents an alkyl group;

$\text{R}_2$  represents a hydrogen atom, an alkyl group, or an aryl group;

$\text{Y}$  represents an alkyl group;

$\text{Y}_1$  and  $\text{Y}_2$  may be the same or different and each represents an alkyl group, an aryl group, an aralkyl group, or a hetero atom-containing aromatic group;

$\text{R}_1$  and  $\text{R}_2$  may be bonded to each other to form a ring;

$\text{R}_2$  and  $\text{Y}$  may be bonded to each other to form a ring;

$\text{Y}_1$  and  $\text{Y}_2$  may be bonded to each other to form a ring;

two or more structures of the general formula (I) may be bonded to each other at any position of  $\text{R}_1$ ,  $\text{R}_2$  or  $\text{Y}$ , or  $\text{Y}_1$  or  $\text{Y}_2$  via a connecting group; and

$\text{X}^-$  represents a non-nucleophilic anion.

3. The positive photosensitive composition as described in claim 2, wherein the resin (B) contains a hydroxystyrene structural unit.

4. The positive photosensitive composition as described in claim 2, wherein the resin (B) contains a monocyclic or polycyclic alicyclic hydrocarbon structure.

5. The positive photosensitive composition as described in claim 4, wherein the resin (B) further contains a repeating unit having a lactone structure.

6. The positive photosensitive composition as described in claim 2, wherein the resin (B) contains a fluorine atom.

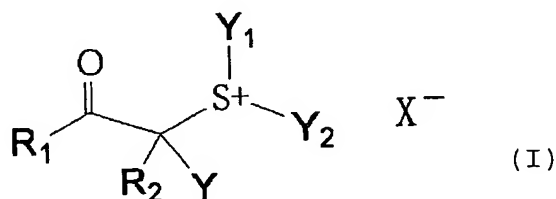
7. The positive photosensitive composition as described in claim 2, which further comprises (C) a dissolution inhibiting compound having a molecular weight of not more than 3,000, which is decomposed by the action of an acid to increase its solubility in an alkaline developer.

8. A positive photosensitive composition comprising:  
(A) a compound capable of generating an acid upon

irradiation with an actinic ray, the compound being represented by the following general formula (I);

(D) an alkaline developer-soluble resin; and

(C) a dissolution inhibiting compound having a molecular weight of not more than 3,000, which is decomposed by the action of an acid to increase its solubility in an alkaline developer:



wherein R<sub>1</sub> represents an alkyl group;

R<sub>2</sub> represents a hydrogen atom, an alkyl group, or an aryl group;

Y represents an alkyl group;

Y<sub>1</sub> and Y<sub>2</sub> may be the same or different and each represents an alkyl group, an aryl group, an aralkyl group, or a hetero atom-containing aromatic group;

R<sub>1</sub> and R<sub>2</sub> may be bonded to each other to form a ring;

R<sub>2</sub> and Y may be bonded to each other to form a ring;

Y<sub>1</sub> and Y<sub>2</sub> may be bonded to each other to form a ring;

two or more structures of the general formula (I) may be bonded to each other at any position of R<sub>1</sub>, R<sub>2</sub> or Y, or Y<sub>1</sub> or Y<sub>2</sub> via a connecting group; and

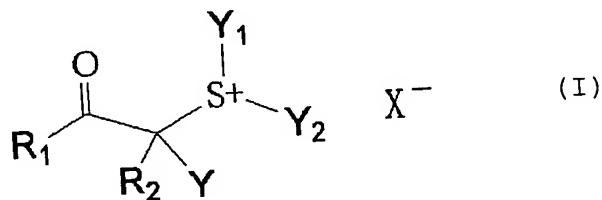
$X^-$  represents a non-nucleophilic anion.

9. A negative photosensitive composition comprising:

(A) a compound capable of generating an acid upon irradiation with an actinic ray, the compound being represented by the following general formula (I);

(D) an alkaline developer-soluble resin; and

(E) an acid crosslinking agent capable of crosslinking with the alkaline developer-soluble resin by the action of an acid:



wherein R<sub>1</sub> represents an alkyl group;

R<sub>2</sub> represents a hydrogen atom, an alkyl group, or an aryl group;

Y represents an alkyl group;

$Y_1$  and  $Y_2$  may be the same or different and each represents an alkyl group, an aryl group, an aralkyl group, or a heteroatom-containing aromatic group;

$R_1$  and  $R_2$  may be bonded to each other to form a ring;

$R_2$  and Y may be bonded to each other to form a ring;  
 $Y_1$  and  $Y_2$  may be bonded to each other to form a ring;  
two or more structures of the general formula (I) may be bonded to each other at any position of  $R_1$ ,  $R_2$  or Y, or  $Y_1$  or  $Y_2$  via a connecting group; and  
 $X^-$  represents a non-nucleophilic anion.

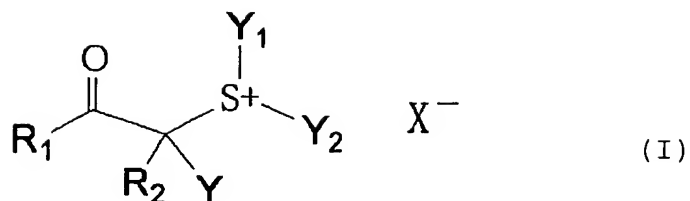
10. The photosensitive composition as described in claim 1, which further comprises (F) a basic compound.

11. The photosensitive composition as described in claim 1, which further comprises (G) a surfactant containing at least one of a fluorine atom and a silicon atom.

12. The photosensitive composition as described in claim 1, wherein each of the  $R_2$  and Y in the formula (I) represents an alkyl group having 1 to 20 carbon atoms.

13. The photosensitive composition as described in claim 1, which further comprises at least one of an arylsulfonium compound and a compound having a phenacylsulfonium salt structure.

14. An acid generator represented by the following general formula (I):



wherein R<sub>1</sub> represents an alkyl group;

R<sub>2</sub> represents a hydrogen atom, an alkyl group, or an aryl group;

Y represents an alkyl group;

Y<sub>1</sub> and Y<sub>2</sub> may be the same or different and each represents an alkyl group, an aryl group, an aralkyl group, or a hetero atom-containing aromatic group;

R<sub>1</sub> and R<sub>2</sub> may be bonded to each other to form a ring;

R<sub>2</sub> and Y may be bonded to each other to form a ring;

Y<sub>1</sub> and Y<sub>2</sub> may be bonded to each other to form a ring;

two or more structures of the general formula (I) may be bonded to each other at any position of R<sub>1</sub>, R<sub>2</sub> or Y, or Y<sub>1</sub> or Y<sub>2</sub> via a connecting group; and

X<sup>-</sup> represents a non-nucleophilic anion.

15. A method of forming a resist pattern, which comprises: forming a film including the photosensitive composition described in claim 1; irradiating the film with an actinic ray; and developing the irradiated film.